

FORM PTO 1449 (modified)

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICELIST OF REFERENCES CITED BY APPLICANT(S)  
(Use several sheets if necessary)

Date Submitted to PTO: October 28, 2003

ATTY DOCKET NO.  
2003-1482SERIAL NO.  
NEWAPPLICANT  
Norio KIMURA et al.FILING DATE  
October 28, 2003

GROUP

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
TR	AA	5,931,722	8/1999	Ohmi et al.			
	AB	5,635,053	6/1997	Aoki et al.			
	AC	5,676,760	10/1997	Aoki et al.			
	AD	5,922,620	7/1999	Shimomura et al.			
	AE	5,996,594	12/1999	Roy et al.			
	AF	6,003,527	12/1999	Netsu et al.			
	AG	6,071,816	6/2000	Watts et al.			
	AH	6,098,638	8/2000	Miyashita et al.			
TR	AI	6,325,698	12/2001	Wada et al.			

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO	
TR	AJ	6-260480	9-16-94	JAPAN			Abst.	
	AK	3-136329	6-11-91	JAPAN			Abst.	
	AL	64-90088	4-5-89	JAPAN			Abst.	
	AM	62-74487	4-6-87	JAPAN			Abst.	
	AN	10-314686	12-2-98	JAPAN			Abst.	
	AO	10-99802	4-21-98	JAPAN			Abst.	
	AP	2 324 750	11/1998	GB				
TR	AQ	0 913 442 A2	5/1999	EP			X	

## OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

AR

Takeshi Hattori et al., "Sixth International Symposium on Cleaning Technology in Semiconductor Device Manufacturing", The Electrochemical Society, October 1999.

EXAMINER

Timothy V. S.

DATE CONSIDERED

10/18/04

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of form with next communication to applicant.

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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO	
UR	AJ	0 806 265 A1	11/1997	EP			X	
	AK							
	AL							
	AM							
	AN							

## OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

UR	AO	Toshiaki Kawane et al., "NEC APPROACH", Semiconductor World, October 1998.
UR	AP	Takeshi Hattori et al., "Contamination Removal by Single-Wafer Spin Cleaning with Repetitive Use of Ozonized Water and Dilute HF", Sony Corporation Semiconductor Company, Japan, September 1998.
UR	AQ	Aoki et al., "A degradation-free Cu/HSQ damascene technology using metal mask patterning and post-CMP cleaning by electrolytic ionized water", Technical Digest, International Electron Devices Meeting (Dec. 7, 1997), pp. 31.1.1 through 31.4.4.

EXAMINER

DATE CONSIDERED

10/18/04